Title (en)
PARTICLE MANIPULATION

Title (de)
TEILCHENMANIPULIERUNG

Title (fr)
MANIPULATION DE PARTICULES

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Application
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Abstract (en)
[origin: DE19713637A1] The invention relates to a method for manipulating particles which are in a plasma crystalline state in a plasma of a carrier gas. According to the method, the particles are subjected at least partly to a plasma treatment and/or applied to the surface of a substrate. A device for manipulating particles in the plasma crystalline state comprises a reaction vessel in which plasma electrodes and at least one substrate are placed. The invention provides an adaptive electrode for creating a low frequency or static electric field at selected sites in the reaction vessel.

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